



Ex 1 Calculate the parabolic rate constant  $B$  for a wafer oxidised in dry  $O_2$

Ex 3 Calculate the activation energies for oxidation in water vapour and in dry O<sub>2</sub> from Fig 13.

These values are in good agreement with

**Ex 5** tTD0.00111> silicon wafer is subjected to th schedule. Sixty



Chlorine is an impurity which enhances the oxidation rate and it is often included, in small amounts, in the oxidising ambient. It is useful in the suppression of stacking faults which can have a detrimental effect on device perfor

